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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/385,666	08/26/1999	ROBERTO SUAYA	002282.P066	9500
75	590 11/20/2002			
•	, SPARKMAN, CAM	EXAMINER		
LEIGH & WHINSTON, LLP ONE WORLD TRADE CENTER, SUITE 1600 121 S.W. SALMON STREET			PHAN, THAI Q	
			2123	
			DATE MAILED: 11/20/2002	<u>!</u>

Please find below and/or attached an Office communication concerning this application or proceeding.

MA

Application No. Applicant(s)

09/385,666

Suaya And Gabillet

Examiner

Office Action Summary

Thai Phan

Art Unit 2123



Υį

	The MAILING DATE of this communication appears	on the cover sheet with the correspondence address
	for Reply	
THE	ORTENED STATUTORY PERIOD FOR REPLY IS SET MAILING DATE OF THIS COMMUNICATION.	
mailing - If the - If NO	g date of this communication. period for reply specified above is less than thirty (30) days, a reply within th	and will expire SIX (6) MONTHS from the mailing date of this communication.
	uply received by the Office later than three months after the mailing date of t I patent term adjustment. See 37 CFR 1.704(b).	his communication, even if timely filed, may reduce any
Status	,	
1) 💢	Responsive to communication(s) filed on Aug 26, 1	999
2a) 🗌	This action is FINAL . 2b) ☑ This act	ion is non-final.
3) 🗆	Since this application is in condition for allowance colosed in accordance with the practice under Ex particles.	except for formal matters, prosecution as to the merits is rte Quayle, 1935 C.D. 11; 453 O.G. 213.
Disposi	tion of Claims	
4) 💢	Claim(s) <u>15-57</u>	is/are pending in the application.
4	4a) Of the above, claim(s)	is/are withdrawn from consideration.
5) 🗆	Claim(s)	is/are allowed.
6) 💢	Claim(s) <u>15-57</u>	is/are rejected.
7) 🗆	Claim(s)	is/are objected to.
8) 🗆	Claims	are subject to restriction and/or election requirement.
Applica	ation Papers	·
9) 🗆	The specification is objected to by the Examiner.	
10)□	The drawing(s) filed on is/are	a) \square accepted or b) \square objected to by the Examiner.
	Applicant may not request that any objection to the d	rawing(s) be held in abeyance. See 37 CFR 1.85(a).
11)□	The proposed drawing correction filed on	is: a) \square approved b) \square disapproved by the Examiner.
	If approved, corrected drawings are required in reply to	to this Office action.
12)	The oath or declaration is objected to by the Exami	ner.
Priority	under 35 U.S.C. §§ 119 and 120	
13)	Acknowledgement is made of a claim for foreign pr	riority under 35 U.S.C. § 119(a)-(d) or (f).
a) [☐ All b)☐ Some* c)☐ None of:	
	1. \square Certified copies of the priority documents hav	e been received.
	2. \square Certified copies of the priority documents hav	e been received in Application No
	 Copies of the certified copies of the priority de application from the International Burelee the attached detailed Office action for a list of the 	
14)	Acknowledgement is made of a claim for domestic	
٠ -	The translation of the foreign language provisiona	
15)	Acknowledgement is made of a claim for domestic	• •
Attachm	- -	pricing and a distance of the short range.
_	otice of References Cited (PTO-892)	4) Interview Summary (PTO-413) Paper No(s).
2) X No	otice of Draftsperson's Patent Drawing Review (PTO-948)	5) Notice of Informal Patent Application (PTO-152)
3) 💢 tri	formation Disclosure Statement(s) (PTO-1449) Paper No(s). 7 & 8	6) Other:

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DETAILED ACTION

This Office action is response to patent application S/N: 09/385,666. Claims 15-57 are pending in this Office action.

Drawings

The drawings are objected to by the draftsperson drawing review (see enclosed PTO Form 948).

Specification

2. It is noted that this application appears to refer subject matter disclosed in prior copending Applications No. 09/052,895 and 09/052,915, filed Mar. 31, 1998. A reference to the prior application must be inserted as the first sentence of the specification of this application.

Also, the current status of all nonprovisional parent applications referenced should be included.

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in-
- (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effect under this subsection of a national application published under section 122(b) only if the international application designating the United States was published under Article 21(2)(a) of such treaty in the English language; or

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- (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that a patent shall not be deemed filed in the United States for the purposes of this subsection based on the filing of an international application filed under the treaty defined in section 351(a).
- 4. Claims 15-57 are rejected under 35 U.S.C. 102(e) as being anticipated by Chen, James, US patent no. 6,414,498 B2.

As per claim 15, Chen anticipates method and system for measuring cross-coupling capacitances in an integrated circuits with feature limitations as claimed (Summary of the Invention). According to Chen, the measurement method includes steps of providing at least first and second wires in a wire interconnection structure (col. 3, lines 10-30), charging interconnect wiring to a predetermined voltage by charging means (col. 3, lines 59-65), performing a first measurement associated with a capacitance of the first wire (col. 5, lines 3559), charging the second wire to the predetermined voltage, recharging the first wire to the predetermined voltage, performing a second measurement associated with a capacitance of the first wire, and calculating a difference between the first and second measurement to determine the cross-coupling capacitance between the first and second wire as claimed (Background of the Invention, col. 5, line 35 to col. 7, line 33).

As per claim 16, Chen anticipates coupling series transistor with configuration as claimed (Fig. 1).

As per claim 17, Chen anticipates applying periodic signals to the transistor gates as claimed (Fig. 1).

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As per claim 18, Chen anticipates applied signals are periodic and synchronous or not simultaneous (col. 5, line 48 to col. 6, line 55).

As per claim 19, Chen anticipates charging and discharging interconnection wires in order.

As per claim 20, Chen anticipates measuring cross-coupling capacitances for multiple wire interconnections.

As per claims 21-22, Chen anticipates means for measuring cross coupling capacitances for multiple neighbor wires and using the same measurement techniques for wire neighbor.

As per claim 23, Chen uses transistors in conjunction with transmission wire for measurement.

As per claims 24-25, Chen anticipates capacitance measurement for wires in multilayer integrated circuit, repeating the measurement over a number of cycle over a timing diagram to compute a correct measurement (cols. 5-6).

As per claims 26 and 27, Chen anticipates measuring charge and current for capacitance measurement.

As per claims 28-31, Chen anticipates logic inverter connected between transmission wires for the test interconnect charging circuit (Fig. 1, block (117)).

As per claim 32, Chen anticipates charging mechanism as claimed for capacitance measurement, namely, charging transmission wire for a cycle time period, discharging for other time cycle, measuring rate of discharging and coupling capacitance (col. 5, lin 35 to col. 7, line 18).

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As per claims 33-34, Chen anticipates transistor in conjunction with transmission wires and effect of neighbor wires in capacitance measure.

As per claim 35, Chen anticipates method and system for measuring cross-coupling capacitances in an integrated circuits with feature limitations as claimed (Summary of the Invention). According to Chen, the measurement method includes means for providing a first and second transistors coupled in series (Fig. 1), means for providing at least first and second wires in a wire interconnection structure (col. 3, lines 10-30), charging interconnect wiring to a predetermined voltage by charging means (col. 3, lines 59-65), performing a first measurement associated with a capacitance of the first wire (col. 5, lines 3559), charging the second wire to the predetermined voltage, recharging the first wire to the predetermined voltage, performing a second measurement associated with a capacitance of the first wire, and calculating a difference between the first and second measurement (substraction) to determine the cross-coupling capacitance between the first and second wire as claimed (Background of the Invention, col. 5, line 35 to col. 7, line 33).

As per claim 36, Chen anticipates low/high logic values feature as claimed.

As per claims 37-38, Chen anticipates a logic coupled to the interconnection wires such logic including inverter, gates, etc. as claimed (Fig. 1).

As per claims 39-41, Chen anticipates the claimed limitations for measurement of crosscoupling capacitance.

As per claim 42, Chen anticipates ammeter for measuring cross-coupling capacitances.

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As per claim 43, Chen anticipates measurement of cross-coupling capacitance for multiple neighbor wires to the first wire.

As per claim 44, Chen anticipates means for measuring cross coupling capacitances for multiple neighbor wires and using the same measurement techniques for wire neighbor.

As per claims 45-46, Chen anticipates capacitance measurement for wires in multilayer integrated circuit, repeating the measurement over a number of cycle over a timing diagram to compute a correct measurement and the measurement is accomplished with library element or with measurement tools (cols. 5-6).

As per claim 47, Chen anticipates method and system for measuring cross-coupling capacitances in an integrated circuits with feature limitations as claimed (Summary of the Invention). According to Chen, the measurement method includes means for providing a first and second transistors coupled in series (Fig. 1), means for providing at least first and second wires in a wire interconnection structure (col. 3, lines 10-30), charging interconnect wiring to a predetermined voltage by charging means (col. 3, lines 59-65), performing a first measurement associated with a capacitance of the first wire (col. 5, lines 3559), charging the second wire to the predetermined voltage, recharging the first wire to the predetermined voltage, performing a second measurement associated with a capacitance of the first wire, and calculating a difference between the first and second measurement (substraction) to determine the cross-coupling capacitance between the first and second wire as claimed (Background of the Invention, col. 5, line 35 to col. 7, line 33).

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As per claims 48-50, Chen anticipates such feature limitations for cross-coupling capacitance measurement.

As per claim 51, Chen anticipates method and system for measuring cross-coupling capacitances in an integrated circuits with feature limitations as claimed (Summary of the Invention). According to Chen, the measurement method includes means for providing a first and second transistors coupled in series (Fig. 1), means for providing at least first and second wires in a wire interconnection structure (col. 3, lines 10-30), charging interconnect wiring to a predetermined voltage by charging means (col. 3, lines 59-65), performing a first measurement associated with a capacitance of the first wire (col. 5, lines 3559), charging the second wire to the predetermined voltage, recharging the first wire to the predetermined voltage, performing a second measurement associated with a capacitance of the first wire, and calculating a difference between the first and second measurement (substraction) to determine the cross-coupling capacitance between the first and second wire as claimed (Background of the Invention, col. 5, line 35 to col. 7, line 33).

As per claim 52, Chen anticipates ammeter being used to measure current for capacitance measurement.

As per claims 53-54, Chen anticipates cross-coupling capacitance in multiple neighbor wires or interconnection wires.

As per claim 55, Chen anticipates multilayer interconnection in an integrated circuit under capacitance measurement.

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As per claim 56, Chen anticipates inverter in conjunction with interconnection wires for capacitance measurement (Fig. 1, cols. 4-6).

As per claim 57, Chen anticipates timing for charging and transistors are not activated simultaneously as claimed (cols. 5-6).

Conclusion

- 5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.
- 1. US patent no. 5,212,454, issued to Proebsting, Robert, on May 1993
- 2. US Patent no. 6,011,731, issued to Beigel et al., on Jan. 2000
- 3. US patent no. 6,249,903 B1, issued to McSherry et al., on June 2001
- 4. US patent no. 6,300,765 B1, issued to Chen, James, on Oct. 2001
- 6. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thai Phan whose telephone number is (703) 305-3812.

Any inquiry of a general nature or relating to the status of this application should be directed to the Group receptionist whose telephone number is (703)305-3900.

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Any response to this action should be mailed to:

Commissioner of Patents and Trademarks

Washington, D.C. 20231

or faxed to:

(703) 746-7239, (for formal communications intended for entry)

Or:

(703) 746-7240 (for informal or draft communications, please label

"PROPOSED" or "DRAFT")

Hand-delivered responses should be brought to Crystal Park II, 2121 Crystal Drive, Arlington. VA., Sixth Floor (Receptionist).

November 12, 2002

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